Eulitha receives order for PHABLE Photolithography System from Changchun Institute of Optics, Fine Mechanics and Physics (CIOMP)

The Changchun Institute, China is the Latest Major Research Center to Start Using the Unique PhableR 100 Nano-Lithography System of the Swiss firm

Wurenlingen, Switzerland, August 18, 2015

EULITHA, a Swiss startup company offering innovative lithography equipment and services for the nanotechnology, photonics and optoelectronic markets announced today that it received a new order for its unique PhableR 100 photolithography tool from the Changchun Institute of Optics, Fine Mechanics and Physics (CIOMP), China. The system incorporating Eulitha's proprietary Displacement Talbot Lithography technology will enable researchers of the renowned institute to print high resolution periodic patterns without the severely limiting requirements such as flatness or conductivity one faces with previously available lithography technologies.

Changchun Institute of Optics, Fine Mechanics and Physics (CIOMP), founded in 1952 by the Chinese Academy of Science, is the first institute dedicated to research in the field of optics in China. The institute runs research programs on luminescence, applied optics, optical engineering, precision machinery and equipment production. Changchun Institute hosts more than 2000 employees; most of which have doctoral degrees. The ordered PhableR 100 photolithography system will be installed at the National Key Laboratory of Applied Physics of CIOMP. The laboratory research fields include crystal optics, micro and nano devices and systems, short-wave optics, optical information integration, information security, space optics and remote sensing. Ms. Xiaoyu Sun, General Manager at GermanTech Co., distributor of PhableR 100 systems in China, said "the order from the Changchun Institute shows the recognition of the value offered by our unique technology. We are looking forward to working with researchers at this leading institute and our colleagues at Eulitha to further demonstrate the versatility and utility of the system to researchers in China and beyond."

The PhableR 100 system is capable of exposing periodic patterns down to feature sizes below 150nm which rivals much more expensive high-end i-line steppers. The patented focus-free imaging technology used by the system enables uniform printing on non-flat samples often found in photonic and optoelectronic sectors. Eulitha had recently announced the delivery of one of their lithography systems to the Twente University in the Netherlands.

Eulitha AG is a spin-off company of the Paul Scherrer Institute, Switzerland. It specializes in the development of lithographic technologies for applications in optoelectronics and photonics. It produces and markets nano-patterned samples and templates using its own PHABLE tools and state-of-the-art e-beam lithography systems. PHABLE is a registered

trade mark and the brand name of Eulutha's proprietary photolithography platform, which includes exposure tools and wafer patterning services.

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